This article was downloaded by: On: 21 January 2011 Access details: Access Details: Free Access Publisher Taylor & Francis Informa Ltd Registered in England and Wales Registered Number: 1072954 Registered office: Mortimer House, 37- 41 Mortimer Street, London W1T 3JH, UK

International Journal of Polymer Analysis and Characterization

Publication details, including instructions for authors and subscription information: <http://www.informaworld.com/smpp/title~content=t713646643>

Quantitative ToF SIMS Analysis of Spun-Cast and Solution-Cast Polymer Films

Alistair M. Leeson^a; Morgan R. Alexander^a; Robert D. Short^a; Martin J. Hearn^b; David Briggs^b **a** Department of Engineering Materials, University of Sheffield, Sheffield, UK ^b ICI plc, Wilton Research Centre, Cleveland, UK

To cite this Article Leeson, Alistair M., Alexander, Morgan R., Short, Robert D., Hearn, Martin J. and Briggs, David(1997) 'Quantitative ToF SIMS Analysis of Spun-Cast and Solution-Cast Polymer Films', International Journal of Polymer Analysis and Characterization, 4: 2, 133 — 151

To link to this Article: DOI: 10.1080/10236669708033942 URL: <http://dx.doi.org/10.1080/10236669708033942>

PLEASE SCROLL DOWN FOR ARTICLE

Full terms and conditions of use:<http://www.informaworld.com/terms-and-conditions-of-access.pdf>

This article may be used for research, teaching and private study purposes. Any substantial or systematic reproduction, re-distribution, re-selling, loan or sub-licensing, systematic supply or distribution in any form to anyone is expressly forbidden.

The publisher does not give any warranty express or implied or make any representation that the contents will be complete or accurate or up to date. The accuracy of any instructions, formulae and drug doses should be independently verified with primary sources. The publisher shall not be liable for any loss, actions, claims, proceedings, demand or costs or damages whatsoever or howsoever caused arising directly or indirectly in connection with or arising out of the use of this material.

Quantitative ToF SIMS Analysis of Spun-Cast and Solution-Cast **Polymer Films**

ALlSTAlR M. LEESONa-*, MORGAN **R.** ALEXANDERa, ROBERT D. SHORT^a, MARTIN J. HEARN^b and DAVID BRIGGS^b

aDepartment of Engineering Materials, University of Sheffield, Sir Robert Hadfield Building, Mappin Street, Sheffield S1 3JD UK; blCl plc, Wilton Research Centre, P.O. Box 90, Wilton, Middlesbrough, Cleveland TS90 8JE UK

(Received 21 October 1996; Revised 29 April 1997)

Films of a series of monodisperse, moderately syndiotactic poly(methy1 methacrylate) (PMMA) standards, with M_w ranging from 2,900-428,000, were solution-cast and spun-cast from chloroform onto clean aluminium substrates. The polymers were thoroughly characterized by conventional spectroscopic and chromatographic techniques. The films were studied using x-ray photoelectron spectroscopy (XPS) and time-of-flight secondary-ion mass spectrometry (ToF **SIMS).** The effects **of** molecular weight and film thickness on **SIMS** spectra were investigated thoroughly by unit-mass and high-resolution ToF **SIMS.** Film thickness had a pronounced effect on the negative **SIMS** spectra, particularly in films a few monolayers thick. This was seen in both the total negative ion counts $(m/z 31-200)$ and the key negative ion intensity ratios. A parallel effect was observed with respect to the effect of molecular weight. These differences are attributed to (i) the original end-group concentration in the surface which decreases with increasing molecular weight and (ii) the original end-group concentration in the surface which increases as film thickness decreases.

Keywords: Time-of-flight secondary-ion mass spectrometry (ToF **SIMS),** poly(methy1 methacrylate), molecular weight, film thickness

^{*}Corresponding author.

Presented at the 9th International Symposium on Polymer Analysis and Characterization, Keble College, Oxford, UK, July 1996.

INTRODUCTION

Time-of-flight secondary-ion mass spectrometry (ToF SIMS) is an established method for the analysis of polymer surfaces.^[1] Many classes of polymers have been studied, such as polystyrenes,^[2] polyamides,^[3] polyurethanes,^[4] polyglycols,^[5] polymethacrylates,^[6] etc. For most of these applications, SIMS has been used in a qualitative nature, that is to distinguish between polymer types by a so called 'fingerprint' spectra.

One polymer that has been well documented in the SIMS literature is poly(methyl methacrylate).^[6-15] It is clear from examination of published spectra of PMMA that marked differences in relative ion intensities exists.. These arise in part from use of different instrumentation (ToF vs. quadrupole), but also from the lack of standardization in material and preparation prior to analysis. While there has been some work on instrumentation parameters, there has been very little on sample related variables, that is additives, molecular weight, polydispersity, solvent, etc. The intrinsic sample properties and sample preparation method all contribute to the SIMS spectra. Their relative importances have not been systematically investigated, Hence, in this paper the effects of molecular weight and film thickness on SIMS spectra of PMMA are investigated.

EXPERIMENTAL

Polymer Evaluation

Four monodisperse poly(methy1 methacrylate) standards were purchased from Polymer Laboratories (Church Stretton, England) with M_{w} values of 2,900, 12,700, 89,100, and 428,000. These will be referred to as samples PMMA-I, PMMA-2, PMMA-3, and PMMA-4, respectively. The polymers were extensively characterized by ¹H nuclear magnetic resonance spectroscopy (NMR), Fourier-transform infrared spectroscopy (FT-IR), and size exclusion chromatography (SEC). These were used to verify the polymer data as supplied, that is molecular weight, polydispersity, and tacticity, and to identify impurities present, if any. Matrix-assisted laser-desorption ionization time-of-flight mass spectrometry (MALDI ToF MS) was used to elucidate the end-groups of the samples.

Surface Analysis

Surface analysis was carried out by x-ray photoelectron spectroscopy (XPS) and ToF SIMS. XPS was carried out using a VG CLAM 2 photoelectron spectrometer (VG Scientific, East Grinstead, England). The operating conditions for XPS analysis using Mg K_{α} x-rays were 100W (10mA, 1OkV). The take-off angle relative to the plane of the sample surface was *30°,* which gave a typical sampling depth of 1.8nm for the Cls electrons.[l6I Survey scan spectra were obtained using a pass energy of 100eV. Two narrow-scan spectra of carbon (Cls) and oxygen **(01s)** core levels were taken using a pass energy of 20eV.

Unit-mass ToF SIMS was carried out on two VG Scientific IX23LS time-of-flight secondary-ion mass spectrometers (VG Scientific, East Grinstead, England). The primary ion source was a FEI liquid metal (Ga⁺) ion source, which gave a beam current of 1nA. The analyzer was a Poschenreider type. For secondary ion extraction the sample was held at **&5kV,** depending on whether positive or negative spectra were being acquired. Charge compensation for insulating samples was achieved by use of a low-energy electron flood gun. The sample bias was reduced to zero during the electron flood cycle to prevent sample damage. The mass information obtained by the detector was transferred to a DigitaVPDP microcomputer via time-to-digital converters. The system was controlled by VGX7000T software.

High-resolution ToF SIMS were recorded on a Physical Electronics PHI 7200 instrument (Eden Prairie, Minnesota, USA). This instrumentation has been extensively described elsewhere in the literature.^[17]

Film Preparation

HPLC-grade hexane, methanol, and chloroform were purchased from Aldrich Chemicals Co. (Gillingham, England) and used as supplied. The glassware used in the sample casting process underwent a rigorous cleaning procedure, which **was** required to minimise the amount surface contamination at the polymer surface. First, a mild abrasive detergent was applied and thoroughly rinsed with distilled water. The glassware was then immersed in 20% concentration nitric acid for 30 min and subsequently rinsed with distilled water. Finally, the glassware was rinsed by HPLCgrade methanol and dried in an oven at 50°C overnight.

For surface analysis, films of PMMA were (i) solution-cast into an aluminium pan and (ii) spun-cast onto aluminium, which was purchased from Fisons Chemicals (Loughborough, England). The aluminium substrate was found to have a hydrocarbon overlayer on the surface. A suitable cleaning procedure was determined for the aluminium substrate by ToF SIMS analysis. The criteria for selecting the cleaning procedure (Table I), was the one which produced the highest $Al^{\dagger}/C_3H_5^{\dagger}$ peak ratio, which was then used throughout the sample casting process. Hence, the aluminium substrate was cleaned by the following procedure: a 15 min soak in hexane, followed by a thorough rinse in distilled water and a 15 min soak in chloroform. The aluminium was subsequently dried in an oven at 50°C overnight.

For solution-cast films 200mg of PMMA sample was dissolved into 10ml of chloroform, that is 2% w/v. The solution was poured into an aluminium pan, partially covered and placed into a fume cupboard. Once the majority of solvent was removed, the aluminium pan was placed in a vacuum oven at 10^{-2} mbar for 24 h, at a preset temperature (50°C), which had previously been determined from XPS measurements.^[18] The films were considered to be of constant thickness, which was calculated to be 66µm, based on the density of PMMA as 1.188 g/cm^{3 [19]}

For spun-cast films, two concentrations were used, 2 and 0.2% w/v. Subsequent to casting, the films were placed in a vacuum oven at 50°C for 24 h. The thicknesses of the spun-cast films were 2μ m and 2nm , respectively for the 2% and 0.2% concentrations. The former was calculated by a cut-and-weigh method, based on the density of PMMA as 1.188 g/cm, $3^{[19]}$ while the latter was calculated by signal substrate signal attenuation XPS.^[20] The air/polymer interface was analyzed for all the films.

TABLE I Observe Al⁺/C₃H₅⁺ Peak Areas Ratios for Various Aluminium Pan Cleaning **Procedures as Determined from ToF-SMS**

Aluminum pan cleaning procedure	Peak area At^*	Peak area $CiHs$ ⁺	Area ratio $Al^{\dagger}/C_3H_5^{\dagger}$	
uncleaned	405807	221406	1.832	
15 min soak in hexane	708992	289030	2.453	
hexane/distilled water/methanol	1064902* ¹	187323	5.684	
hexane/distilled water/chloroform	1296202**	45329	28.595	

* **15 min soak in hexane followed by thorough rinse in distilled water, with final 15 min soak in either methanol or chloroform.**

[†] Dried in an oven at 50°C overnight.

RESULTS AND DISCUSSION

Polymer Evaluation

The results of polymer evaluation are shown in Table 11. The tacticity of the samples was determined by ratioing the integrals of the methyl peaks in the **'H NMR** spectra. This showed that the samples are moderately syndiotactic. The molecular weight and polydispersity were determined using a polystyrene calibration curve. **No** presence of impurity was observed in the **FT-IR** or **NMR** spectra and no oligomeric species were present in the **SEC** chromatograms. Thus the samples were considered to be 'contaminant free'. The end-groups of the **PMMA-1** and **PMMA-2** were determined by **MALDI** ToF MS and were shown to be hydrogen-terminated, for example in the case of Figure **1,** which shows the **MALDI** ToF **MS** for **PMMA-1,** m/z 2325 is interpreted as sodium cationized [H-(MMA)₂₃-H]. The endgroups for the other samples were obtained from the supplier.

X-ray Photoelectron Spectroscopy (XPS)

A survey scan **XPS** spectrum for a **PMMA-2** is shown **in** Figure 2. The spectrum contains two primary peaks, **Cls** at *cu.* 285eV and **01s** at ca. 533eV. Figure 3 shows a narrow scan spectrum of the **Cls** peak. The **Cls** curve was fitted with four contributions. The most intense is due to the carbon bound to carbon and/or hydrogen centred at 285eV. The other three peaks are due to CCH₂CH₃, OCH₃, and O-C=O, which are shifted from the main peak by 0.8, 1.8, and **4.0** eV, respectively.[211 In the **01s** narrow scan, two peaks of equal intensity were fitted at *ca.* 533.9eV for $Q=$ c and the other for **Q-C** at *cu.* 535.5eV.

PMMA Sample	$M_{\rm w}$	Polydispersity	mm^*	mr^*	rr^*	End Groups
PMMA-1	2.900	1.14	55%	34%	11%	$H-(MMA^{\dagger})$ _n -H
PMMA-2	12.700	1.08	54%	38%	8%	$H-(MMA)$ H
PMMA-3	89.100	1.09	51%	44%	5%	$C_6H_5C(CH_3)_2$ -(MMA) _n -H
PMMA-4	428,000	1.18	55%	40%	5%	$C_6H_5C(CH_3)_2$ -(MMA) _n -H

TABLE I1 Polymeric Data for PMMA Samples

***m and r refer to meso and racemic diads, respectively.**

+MMA refers to methyl methacrylate repeat unit.

FIGURE 1 MALDI ToF MS of PMMA-1 for end-group determination.

Downloaded At: 17:02 21 January 2011

Downloaded At: 17:02 21 January 2011

Time-of-Flight Secondary-Ion Mass Spectrometry

Polydimethylsiloxane was detected in some initial positive ion spectra with typical peaks at m/z 73, 147, and 207. This was effectively removed from the surface after the sample was ultrasonically cleaned for 1 min in HPLCgrade hexane. Hence, this process was adopted for all sample surfaces prior to analysis. The ultrasonic cleaning process has been thoroughly investigated,^[18] and these results showed that this process does not degrade the polymer or have any effect on the quantification of SIMS data.

Positive and negative ion spectra of PMMA are shown in Figures 4a and 4b, respectively. At low mass in the negative ion spectra $\left(\frac{*m*}{2}\right)$, the peaks that dominate are of very high *peak* intensity, that is **H-, C-, CH-,** *0-,* OH-, C_2^- , and C_2H^- , and give no chemical information relating to the structure of the polymer. Characteristic key ions of PMMA are observed at m/z 31, 41, *55, 85,* 87, 101, 141, and 185. In the positive ion spectra, characteristic key ions are observed at m/z 59, 69, 115, 126, and 186. In addition, the positive ions m/z 139, 233, and 235 were selected on their prominence in their respective mass range. The structural formulae of the ions were unambiguously determined on the PHI 7200. These formulae are shown in Table III.

To allow us to identify differences in the samples, with respect to molecular weight and film thickness, the SIMS data were analyzed by the following methods:

- 1. Measurement of the absolute peak intensity.
- 2. Normalization- the absolute peak intensities of the peak of interest is normalized over a mass range (m/z) 0-400 for positive ions and m/z 31-200 for negative ions). The criteria used in the selection of these ranges have been stated elsewhere.^[18]
- 3. Ion intensity ratios. The absolute peak intensity is ratioed by the intensity of a base molecular-ion peak in the spectra (m/z) 59 for the positive ions and m/z 31 for the negative ions).

Also, to establish the level of spectral reproducibility, standard errors were employed. The standard errors used have been calculated elsewhere.^[18]

Effect of Molecular Weight

The effect of molecular weight on the SIMS spectra has been investigated quantitatively for all films and the absolute negative ion intensities are given in Table IV. Figure 5 shows a plot of the total negative ion counts

FIGURE 4 (a) Positive SIMS spectra (b) Negative SIMS spectra.

 $(m/z 31-200)$ vs. the log molecular weight of the PMMA sample. From this figure it can be seen that the total negative ion intensity decreases with increasing molecular weight. Figure 6 shows negative ion intensity ratios based on m/z 31, which are significantly affected by molecular weight, that is 85/31, 87/31, and 101/31. The ion ratios 41/31, 55/31, 141/31, and 185/31 were found to be constant over the molecular weight range and are ot shown. The figure shows that at molecular weights >90,000 the **PMMAs** are indistinguishable. No obvious trends were seen in the positive ion Downloaded At: 17:02 21 January 2011 Downloaded At: 17:02 21 January 2011

^tspun cast

FIGURE *5* **Total negative ion counts** *(dz* **31-200) for solution-cast PMMA films.**

HGURE **6 Negative** ion **intensity ratios based on** *m/z* **31 for solution-cast PMMA films: 85/31** (+), **87/31 (x), 101/31** *(0).*

spectra, which appear to remain constant with increasing molecular weight. This result is in good agreement with previous findings, $^{[18,22]}$ which speculate that the secondary ion yield for each ion is very similar. This result is attributed to the low probability of positive ions forming from original endgroups, that is positive ions originate from the polymer main chain.

The assignments of the m/z 87 and 101 were identified in a study of a low-molecular-weight PMMA oligomer $(M_w \sim 1890)$ and originate from original polymer end-groups, that is fully saturated.^[12] The end-groups of PMMA-1 and PMMA-2 have already been established to be hydrogenterminated, hence it is anticipated that these end-groups produce the m/z 87 and 101 ions. From the observed decrease in the m/z 87/31 and 101/31 ion ratios, with increasing molecular weight (Fig. *5),* it is proposed that this effect arises as a result of a decrease in the surface original polymer-end group concentration. Hence, at low molecular weight the largest contribution to the relative ion intensities would be predominantly from the original end-groups, with a small contribution from the fragmentation of the polymer main chain. **As** molecular weight increases, the contribution from the original chain-ends decreases, up to a point $(M_w > 90,000)$ where the contribution is predominantly from polymer main chain with only a small contribution, if any, from original end-groups.

The origin of the m/z 85 ion has been assigned to a new polymer endgroup, created as a result of a primary ion beam impact.^[12] However, the contribution of this new end-group is not thought to be significant. Although these end-groups are seen in cationized fragments emitted from submonolayer films of low-molecular-weight PMMAs on silver, the situation here is very different. Chain entanglements will inhibit the emission of whole molecules. It is therefore proposed that the major contribution to the intensity of the m/z 85 ion at low molecular weight is predominantly from the original polymer end-groups, that is m/z 87-2H, with a minor contribution from the fragmentation of the polymer main chain. As the molecular weight increases, the contribution from the original chain-ends decreases, up to a point $(M_w > 90,000)$ where the contribution is predominantly from polymer main chain with only a small contribution, if any, from original end- groups.

The original end-groups of the other PMMA samples, that is PMMA-3 and PMMA-4 are cumyl and hydrogen. There is no spectral evidence for the presence of the cumyl end-groups. The dominant contribution for *m/z* **85,87,** and **101** for these is from the polymer backbone with only a minor, if any, contribution from the original end-groups. Otherwise, the negative ion spectra of PMMAs with $M_w > 90,000$ are indistinguishable.

Effect of Film Thickness

The effect of thickness on the **SIMS** spectra of **PMMA** has been investigated quantitatively for all the samples. The absolute negative ion intensities for all the peaks monitored in the various films are shown in Table **IV.** Figure 7 shows the total negative ion counts $(m/z 31-200)$ vs. the log molecular weight for all thicknesses. This data clearly indicates two distinct trends. Firstly, total negative ion counts decrease as molecular weight increases in all the films. This is in very good agreement with earlier work on the effect of molecular weight in solution cast films.^[18] Secondly, within a molecular weight regime, the total negative ion intensity decreases as film thickness increases. This observation is also illustrated in Table **V,** which shows the negative ion ratios that displayed the greatest effect with respect to molecular weight based on m/z 31 for the film thicknesses studied.

From the observed trend it is proposed that the surface concentration of original polymer end-groups increases as the polymer film thickness

FIGURE 7 Total negative ion counts $(m/z 31-200)$ for varying thicknesses of PMMAs: **66ym** (+), 2ym **(D),** 2nm *(0).*

TABLE V Negative Ion Ratios Based on m/z 31 for Varying Thicknesses of a Series of PMMAs Cast on to an Aluminium Substrate

¹thickness calculated by signal substrate signal attenuation XPS.

 $^{\rm t}$ thickness calculated by cut and weigh method $^{\rm t}$ solution cast

l,

Downloaded At: 17:02 21 January 2011

Downloaded At: 17:02 21 January 2011

decreases. Hence, at low molecular weight the largest contribution to the relative ion intensities, m/z 87 and 101, would be predominantly from the original end-groups, with a small contribution from the fragmentation of the polymer main chain (Fig. **8). As** thickness increases, the surface concentration of original chain-ends decreases, probably up to a point where the contribution is no longer significant. Positive ion spectra were once again uninformative.

From this study, it is apparent that the negative ion intensity ratios and total ion counts are both molecular weight and thickness dependent. **It** is proposed that these factors can be explained by the following: (i) the surface end-group concentration decreases with increasing molecular weight and (ii) the surface end-group concentration increases as film thickness decreases. Theoretical models based on molecular dynamic and Monte-Car10 simulations of semicrystalline systems predict an excess **of** chainends at the surface.^[23,24] This behavior has been proved in amorphous polymer surfaces.[25] Other recent work has also shown polymer surfaces enriched by chain-ends.^[26,27] A 2-fold chain-end enrichment was observed in the top 1nm of isotopically end-capped polystyrene $(M_w \sim 10,000)$ by high-resolution electron energy loss spectroscopy.^[26] A static SIMS study of diblock and triblock copolymers of hydrogenous and deuterated

FIGURE 8 Negative ion intensity ratios m/z 87/85 (\bullet) and 101/85 (\bullet) for solution-cast **PMMA film.**

polystyrene $(M_w \sim 10,000)$ indicated the surface chain-end concentration was up to 400% of the bulk value This was found to be independent of any isotope effects.^[27]

Recently, it was proposed that chain-end enrichment would significantly lower the surface glass-transition temperature (T_g) .^[25] This behaviour has been reported experimentally by Keddie *et al.*^[28] They found that T_e was decreased with decreased thicknesses of polystyrene films. From these results it was postulated that a 'liquid-like' layer exists at the surface, which is independent of molecular weight.^[28] This behaviour was observed in a subsequent study with PMMA on gold surfaces.^[29] From our results we speculate that there is **a** large surface concentration of end-groups at low molecular weight. When the polymer chain length increases, the end-group concentration decreases, up to a point where this concentration becomes independent of molecular weight. Within a molecular weight regime, the surface concentration of original polymer end-groups decreases as the film thickness increases.

CONCLUSIONS

The effects of molecular weight and film thickness on ToF SIMS spectra have been systematically investigated for a series of poly(methy1 methacrylates). Negative ion spectra were found to be susceptible to sample variables, but the positive ion spectra were very uninformative. Both molecular weight and film thickness had a pronounced effect on the **SIMS** spectra seen in both the total negative ion counts and negative ion intensity ratios, Figures *5,6,* and 7. The effects are explained as follows: (i) the original surface end-group concentration decreases with increasing molecular weight and (ii) the surface end-group concentration increases as film thickness decreases. These results obtained complement other SIMS studies of surface enrichment by polymer end-groups.^[27,30,31]

Acknowledgements

The authors would like to thank Hilary Yates (ICI, Wilton) for the MALDI ToF MS and Alan Bunn (ICI, Wilton) for 'H NMR analysis. **R.D.** Short acknowledges gratefully the support of EPSRC and ICI for the CASE Award for A.M. Leeson that made this work possible.

References

- **[I]** Briggs, D. **(1992)** In *Practical Surface Analysis (2nd ed.) Vol. 2: Ion and Neutral Spectroscopy;* D. Briggs and M.P. Seah, (eds.) (Chichester, Wiley) pp **367-423.**
- **[2]** Chiarelli, **P.** M., Bletsos, I. V., Hercules, D. M., Feld, **H.,** Leute, A. and Benninghoven, A. **(1992)** *Macromolecules,* **25,6970.**
- **[3]** Briggs, D. **(1987)** *Org. Mass. Spec.,* **22,91.**
- **[4]** Hearn, M. **J.,** Briggs, D. and Ratner, B. D. **(1988)** *Macromolecules,* **21,2950.**
- **[5]** Hittle, L. R., Atland, D. E., Proctor, A. and Hercules, D. M. **(1994)** *Anal. Chem.,* **66, 2302.**
- **[6]** Briggs, D. and Hearn, M. **J. (1988)** *Surf: lnrerface Anal.,* **11, 198.**
- **[7]** Gardella, **J. A.** and Hercules, D. M. **(1980)** *Anal. Chem.,* **52, 226.**
- *[8]* Briggs, D. **(1982)** *Surf: Interface Anal.,* **4, 151.**
- 191 Briggs, D., Hearn, M. J. and Ratner, B. D. **(1984)** *Surf: Interface Anal.,* **6, 184.**
- [lo] Brown, A. and Vickerman, J. C. **(1986)** *Surf: Interface Anal.,* **8,75.**
- **[ll] Brinkhuis, R.** G. H. and van Ooij, W. J. **(1988)** *Surf: Interface Anal.,* **11,214.**
- **[12]** Lub, **J.** and Benninghoven, A. **(1989)** *Org. Mass Spec.,* **2.4,164.**
- **[13]** Zimmerman, P. **A.,** Hercules, D. M. and Benninghoven, A. **(1993)AnaL** *Chem.,* **65,983.**
- **[14]** Zirnrnerman, P. **A.** and Hercules, D. M. **(1994)Appl.** *Spec.,* **48,620.**
- **[I51** Eynde, **X.** V., Weng, L. T. and Bertrand, P. **(1997)** *Surf: Interface Anal.,* **25.41.**
- **[I61** Briggs, D. **(1992)** In *Practical Surface Analysis (2nd Ed.) Vol. I: Auger and X-ray Photoelectron Spectroscopy;* D. Briggs and M.P. Seah, (Chichester, Wiley) p. **443.**
- **[I71** Riechlmaier, **S.,** Hammond, J. S., Hearn, M. **J.** and Briggs, D. **(1994)** *Surf: Interface Anal.,* **21,739.**
- **[18]** Leeson, A. **M.,** Alexander, M. R., Short, R. D., Hearn, M. J. and Briggs, D. **(1997)** *Surf: Interface Anal.,* **25,261.**
- **[19]** Gall, W. G. and McCrurn, N. G. **(1961)** *J. Polym. Sci.,* **50,489.**
- **[20]** Seah, M. P. and Dench, W. **A. (1979)** *Surf: Interface Anal.,* **1,2.**
- **[21]** Beamson, G. and Briggs, D. **(1992)AnaL** *Chem.,* **64,1729.**
- **[22]** Leeson, **A.** M., Alexander, M. R., Short, R. D., Hearn, M. **J.** and Briggs, D. *Surf: Interface Anal.,* submitted.
- **[23] Kumar, S. K.,** Vacatello, M. and Yoon, D. **Y. (1988)J.** *Chem. Phys.,* **89,5206.**
- **[24]** Harris, **J.** G. **(1992)** *J. Chem. Phys.,* **96,5077.**
- **[25]** Mayes, A. M. **(1994)** *Macromolecules,* **27,3114.**
- **[26]** Botelho do Rogo, A. M., Lopes de **Silva,** J. D., Rei Vilar, M., Schott, M., Petitjean, S. and Jerome, R. **(1993)** *Macromolecules,* **26,4986.**
- **[27]** Affrossman, *S.,* Hartshome, M., Jerome, R., Pethrick, R. A,, Petitjean, S. and Rei Vilar, M. **(1993)** *Macromolecules,* **26,6251.**
- **[28]** Keddie, **J.** L., Jones, R. **A.** L. and Cory, R. A. **(1994)** *Europhys. Lett.,* **27,59.**
- **[29]** Keddie, **J. L.,** Jones, R. **A.** L. and Cory, R. **A. (1994)** *Faraday Discuss.,* **98,219.**
- **[30]** Briggs, D., Chan, H., Hearn, M. J., McBriar, D. 1. and Munro, H. S. **(1990)** *Langmuir,* **6,420.**
- **[31]** Shard, **A.** G., Davies, M. C. and Schacht, E. **(1996).** *Surf: Interface Anal., 24,787.*